

AR-N 4400.05

Substrate preparation:

Dehydration step: bake on hotplate at 200°C for 15 minutes

Spincoat wafer with HMDS (@4000rpm) and bake on hotplate at 200°C for 2 minutes

tone negative

special

reference http://www.allresist.com/wp-content/uploads/sites/2/2014/03/allresist_produkinfos_ar-n4400_englisch.pdf

spincoat 1000rpm 5µm

4000rpm 1.4µm

prebake 2 minutes @ 90°C on hotplate

After baking put power of hotplate on 0% and let the hotplate cool down to 60°C.

exposure DMO-ML2: Dose = $\pm 45 \text{mJ/cm}^2$ (for 0.6 and 5µ 405nm lasers), $\pm 50 \text{mJ/cm}^2$ (for 1µ 405nm laser)

HBG_uMLA: D = 50mJ/cm^2 (pneumatic focussing, defoc -4)

postbake 5 minutes @ 100°C on hotplate

development 75s in MF321

DI water for 30s